

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 07-169753

(43)Date of publication of application : 04.07.1995

(51)Int.Cl.

H01L 21/3065
C23F 4/00
H01L 21/205
H01L 21/31

(21)Application number : 06-272011

(71)Applicant : HITACHI LTD
HITACHI TECHNO ENG CO LTD

(22)Date of filing : 07.11.1994

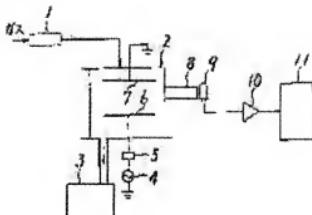
(72)Inventor : IKUHARA SHIYOUJI
SATO HITOAKI
OKIGUCHI MASASHI
KONO TOMOYUKI
KAGE ISAMU

(54) METHOD FOR CLEANING PLASMA TREATING DEVICE

(57)Abstract:

PURPOSE: To provide a method for cleaning plasma treating devices by which the availability of a plasma treating device can be improved and, at the same time, the reproducibility of the processability can be improved by making the treating chamber of the device cleanable without breaking the vacuum in the chamber after the plasma treatment of samples is completed in the chamber.

CONSTITUTION: When the plasma treatment of a prescribed number of samples is completed under a vacuum condition in a treating chamber 2, the samples are taken out from the chamber 2 and, after the gas remaining in the chamber 2 is discharged without opening the chamber 2 against the atmosphere, a cleaning gas is introduced into the chamber 2. Then the inside of the chamber 2 is cleaned with plasma by generating the plasma from the cleaning gas in the vacuum and completion of the cleaning is confirmed by monitoring the cleaned state of the inside.



LEGAL STATUS

[Date of request for examination] 07.11.1994

[Date of sending the examiner's decision of
rejection]

[Kind of final disposal of application other than
the examiner's decision of rejection or
application converted registration]

[Date of final disposal for application]

[Patent number] 2501180

[Date of registration] 13.03.1996

[Number of appeal against examiner's
decision of rejection]

[Date of requesting appeal against examiner's
decision of rejection]

[Date of extinction of right] 24.04.2005